

| Form PTO 1449<br>(Modified)  |                 | U.S. DEPARTMENT OF COMMERCE<br>PATENT AND TRADEMARK OFFICE   |          | ATTY DOCKET NO.<br><b>251475US3DIV</b>      |             | SERIAL NO.<br><b>New Application</b>  |  |
|--|-----------------|--|----------|---|-------------|---|--|
| LIST OF REFERENCES CITED BY APPLICANT  |                 |  |          | APPLICANT<br><b>Kousaku MATSUNO, et al.</b> |             |   |  |
|  |                 |  |          | FILING DATE<br><b>Herewith</b>              |             | GROUP   |  |
|  |                 |  |          |   |             |   |  |
| <b>U.S. PATENT DOCUMENTS</b>   |                 |  |          |   |             |   |  |
| EXAMINER INITIAL   | DOCUMENT NUMBER | DATE   | NAME     | CLASS                                       | SUB CLASS   | FILING DATE IF APPROPRIATE  |  |
| <i>MK</i>  | AA              | 6,080,531  | 06/27/00 | Carter et al.                               |             |   |  |
|  | AB              | 5,971,368  | 10/26/99 | Nelson et al.                               |             |   |  |
|  | AC              | 5,983,909  | 11-1999  | Yeol et al.                                 |             |   |  |
|  | AD              | 6,920,777  | 09-2001  | Imaoka et al.                               |             |   |  |
|  | AE              | 6,325,359  | 12-2001  | Haga et al.                                 |             |   |  |
|  | AF              | 5,503,708  | 04-1996  | Koizumi et al.                              |             |   |  |
|  | AG              | 6,086,057  | 07-2000  | Mitsumori et al.                            |             |   |  |
|  | AH              | 6,039,815  | 03-2000  | Yeol et al.                                 |             |   |  |
|  | AI              | 6,035,871  | 03-2000  | Eui-Yeol, Oh                                |             |   |  |
|  | AJ              | 4,812,201  | 03-1989  | Sakai et al.                                |             |   |  |
|  | AK              | 5,783,790  | 07-1998  | Mitsumori et al.                            |             |   |  |
|  | AL              | 6,217,665  | 04-2001  | Suzuki                                      |             |   |  |
| <i>MK</i>  | AM              | 5,739,575  | 04-1998  | Numano et al.                               |             |   |  |
|  | AN              |  |          |   |             |   |  |
| <b>FOREIGN PATENT DOCUMENTS</b>  |                 |  |          |   |             |   |  |
|  |                 | DOCUMENT NUMBER  | DATE     | COUNTRY                                     | TRANSLATION |   |  |
|  |                 |  |          |   | YES         | NO  |  |
| <i>MK</i>  | AO              | 8-78372  | 03-1996  | Japan (w/ abstract)                         |             | xx  |  |
| <i>MK</i>  | AP              | 63-271938  | 11-1988  | Japan (w/ abstract)                         |             | xx  |  |
|  | AQ              |  |          |   |             |   |  |
|  | AR              |  |          |   |             |   |  |
|  | AS              |  |          |   |             |   |  |
|  | AT              |  |          |   |             |   |  |
|  | AU              |  |          |   |             |   |  |
|  | AV              |  |          |   |             |   |  |
| <b>OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)</b>   |                 |  |          |   |             |   |  |
| <i>MK</i>  | AW              | S. Nelson: Using an ozone water last cleaning process to research the effects of process parameters on water contamination; SPWCC, pp. 230-242, March 4-7, 1996  |          |   |             |   |  |
|  | AX              | M. Hiroshi et al.: Dissolved-Gas Controlled Ultrapure Water Production System for Wet Cleaning Processes; The seventh International symposium on semiconductor manufacturing, proceedings of ISSM '98, Tokyo, pp. 428-431 (1998) |          |   |             |   |  |
|  | AY              | M. Hiroshi et al.: Advanced UCT Cleaning Process Based on Specific Gases Dissolved Ultrapure Water; The eighth International symposium on semiconductor manufacturing, proceedings of ISSM '99 Tokyo, pp. 453-456 (1999)         |          |   |             |   |  |
| <i>MK</i>  | AZ              | M. Hiroshi et al.: Development of ozonated ultra-pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, 2000   |          |   |             | <input checked="" type="checkbox"/> Additional References sheet(s) attached |  |
| Examiner <i>[Signature]</i>  |                 |  |          | Date Considered <i>01/07/05</i>             |             |   |  |
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|  |     |   |  | FILING DATE<br>Herewith              |  | GROUP                         |  |
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| N/K  | AAA | T. Ohmi et al.: Native oxide growth and organic impurity removal on Si surface with ozone injected ultrapure water, J. Electrochem. Soc., 140(3), 804-810, 1993 |  |                                      |  |                               |  |
| N/K  | AAB | Werner Kern. Handbook of Semiconductor Cleaning Technology, 1993, Noyes Publications, Page 120.   |  |                                      |  |                               |  |
|  | AAC |   |  |                                      |  |                               |  |
|  | AAD |   |  |                                      |  |                               |  |
|  | AAE |   |  |                                      |  |                               |  |
|  | AAF |   |  |                                      |  |                               |  |
|  | AAG |   |  |                                      |  |                               |  |
|  | AAH |   |  |                                      |  |                               |  |
|  | AAI |   |  |                                      |  |                               |  |
|  | AAJ |   |  |                                      |  |                               |  |
|  | AAK |   |  |                                      |  |                               |  |
|  | AAL |   |  |                                      |  |                               |  |
|  | AAM |   |  |                                      |  |                               |  |
|  | AAN |   |  |                                      |  |                               |  |
|  | AAO |   |  |                                      |  |                               |  |
|  | AAP |   |  |                                      |  |                               |  |
|  | AAQ |   |  |                                      |  |                               |  |
| Examiner   |     |   |  |                                      |  | Date Considered 01/07/05      |  |
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